

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Patent Application of

CHEN et al.

Atty. Ref.: 2476-37; Confirmation No. 2846

Appl. No. 10/730,381

TC/A.U. 2815

Filed: 09 December 2003

Examiner: Jackson Jr., Jerome

For: PROGRAMMABLE PHOTOLITHOGRAPHIC MASK BASED ON  
SEMICONDUCTOR NANO-PARTICLE OPTICAL MODULATORS

\* \* \* \* \*

February 14, 2007

Mail Stop AF  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

**AMENDMENT AFTER FINAL REJECTION**

Responsive to the Official Action dated August 14, 2006 (for which petition is made for any necessary extension of time), please amend the above-identified application as follows: